



Sheet 1 of 1

PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO: <i>EV-2</i>	SERIAL NO.: <i>10/090,465</i>
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	APPLICANT: <i>Livesay et al.</i>	RECEIVED JUL 16 2003 GROUP 1700 <i>1756</i>
(Use several sheets if necessary)	FILING DATE: <i>3/4/2002</i>	

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>Cuy</i>	AA	2001/0016302 A1	8/23/2001	HIRAYANAGI, ET AL	<i>430</i>	<i>322</i>	
<i>Cuy</i>	AB	5,003,178	3/26/1991	LIVESAY	<i>250</i>	<i>492.3</i>	
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

							TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
<i>Cuy</i>	AL	WO 96/36070	11/14/1996	PCT				
	AM							
	AN							
	AO							
	AP							

OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)

<i>Cuy</i>	AQ	Olson, Kurt A., et al "Characterization, modeling and design of an electrostatic chuck with improved wafer temperature uniformity. Rev. Sci. Instrum. 66 (2) February 1995.
<i>Cuy</i>	AR	Electrostatic Wafer Holder for Wafer Cooling During Reactive Ion Etching. IBM Technical Disclosure Bulletin Vol. 31, No. 1, June 1988 Armonk, New York
	AS	

EXAMINER *Alan G...* DATE CONSIDERED *10/03*

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO: EV-1		SERIAL NO.: <div style="font-size: 1.5em; margin-top: 10px;">10/090,465</div>	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: WILLIAM R. LIVESAY, ET AL.			
(Use several sheets if necessary)		FILING DATE: <div style="font-size: 1.2em; margin-top: 5px;">3/4/2002</div>		GROUP: <div style="font-size: 1.2em; margin-top: 5px;">1756</div>	

U.S. PATENT DOCUMENTS							
EX INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
Cuy	AA	6,319,655 B1	11/20/2001	WONG, ET AL.	430	311	
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						

FOREIGN PATENT DOCUMENTS							TRANSLATION	
DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO		
AI								
AJ								
AK								
AL								
AM								
AN								
AO								

OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)	
Cuy	AP "Synthesis of Siloxanes and Silsesquioxanes for 157 nm Microlithography", Houg V. Tran, et al. Polymeric Materials: Science & Engineering 2001, 84.xxxx.
Cuy	AQ "Electron Beam Processing of Deep-UV Resist", M.F. Ross, et al. Pages 02-19
Cuy	AR "157 nm Resist Materials: Progress Report", Colin Brodsky, et al. Dept. of Chemistry and Chemical Engineering, The University of Texas at Austin, Austin, Texas 78735. Pages 3396-3401
Cuy	AS "E-Beam Stabilization of ArF (193nm) Photoresist for Implementation of Sub-100nm Devices", Cha-Won Koh, et al. Memory R&D Division, Hynix Semiconductor, Inc., Pages 02-11.
Cuy	AT "Organic Imaging Materials: A View of the Future", Michael D. Stewart, et al. Journal of Physical Organic Chemistry, J. Phys. Org. Chem. 2000; 13: 767-774
EXAMINER	DATE CONSIDERED

10/03

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.